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Final Program

The seminar will take place in the lecture hall at
PTB, Hermann-von-Helmholtz building, Abbestr 2-12, 10587 Berlin.
ready to print: [final_program_day1.pdf](#) [final_program_day2.pdf](#)

Thursday, November 5th

09:00		Registration & Poster Setup	
10:00	F. Scholze	Opening and Overview of PTB Activities in VUV and EUV Metrology	PTB
		Session I: EUVL	
10:20	V. Banine	EUV lithography now	ASML
10:40	H. Enkisch	Overview of EUV Lithography at Carl Zeiss SMT: status and trends in optical coatings	CZ SMT
11:00	A. Ullrich	Recent developments in EUV photomask metrology	AMTC
11:20	Y. Ekinici	Scanning coherent diffraction imaging techniques for EUV photomask metrology	PSI
11:40	P. Naujok	Beyond-EUV multilayer coatings for next generation lithography	IOF
12:00		Lunch	
13:00		Poster Session	
		Session II: Sources & Instrumentation for EUV	
14:20	A. Meseck	Accelerator based EUV Sources	HZB
14:40	T. Mey	Beam diagnostics at EUV wavelengths	LLG
15:00	J. Vieker	Compact discharge based EUV Source for metrology and inspection	ILT
15:20	L. Juschkin	Application of lens-less imaging techniques for nano-scale microscopy employing plasma-based EUV source	RWTH
15:40	U. Kleineberg	Cr/Sc ML mirrors for isolated attosecond pulses	LMU
16:00		Coffee Break	
		Session III: Space instrumentation	
16:40	U. Arp	Improved Ultraviolet Metrology Capabilities at SURF III	NIST
17:00	R. Schäfer	Absolute UV/EUV detection based on ionization chamber measurements	IPM
17:20	M. Caldwell	VUV calibration of the space-flight solar instrument SPICE at MLS	RAL
17:40	S. Gissot	EUV characterization of (P43/P46) phosphor coated FSI CMOS image sensors for solar observations	ROB
18:00			
19:00		Get Together, Dinner Buffet	
22:00		End of Day 1	

Friday, November 6th

08:30		Opening of Day 2	
		Session IV: Scatter techniques	
08:40	V. Holy	Diffuse x-ray reflection from randomly rough multilayers - beyond the standard fractal model	U Prague
09:00	A. Haase	Interface properties of multilayer mirrors with sub-nanometer layer thicknesses	PTB
09:20	A. Maryasov	EUV scattering metrology with high-brightness discharge plasma source	RWTH
09:40	S. Heidenreich	Comparison of sampling methods and application to scatterometry	PTB
10:00		Coffee Break	
		Session V: Spectroscopy & Surfaces	
10:40	E. teSligte	EBL2, a flexible and controlled EUV exposure and surface analysis system	TNO
11:00	D. Bleiner	Concomitant surface microscopy and spectroscopy in the lab enabled by plasma-driven XUV	EMPA
11:20	I. Mantouvalou	Novel Spectroscopic Schemes using a Highly Brilliant Laser-Produced Plasma Source	TUB
11:40	J.I. Larruquert	Optical-constant metrology of VUV thin-film materials	CSIC
12:00		Lunch	
		Session VI: Optics & Materials	

13:20	T. Feigl	EUV optics with integrated IR suppression gratings	Optixfab
13:40	A. Gatto	Last developments for high end optical gratings and microstructured optics	CZ Jena
14:00	F. Siewert	On the characterization of ultra-precise mirrors for use at FEL-beamlines by use of slope measuring	HZB
14:20	E. Meltcahkov	Design, deposition and metrology of EUV multilayer coatings for SR, FEL and space applications	IO/LCF
14:40	K. Nikolaev	High resolution X-ray diffraction in extremely asymmetrical condition	U Twente
15:00	S. Yulin	Interface-engineered EUV/Soft X-ray multilayer mirrors	IOF
15:20	A. Gottwald	Wrap-up and Closing	PTB
15:30		End of the Seminar	

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